

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Applicants: Tebery, et al.

Serial No.: 10/791,259

Filed: March 2, 2004

Title: LITHOGRAPHY MASK UTILIZING ASYMMETRIC LIGHT SOURCE

Examiner: Elisabeth Abraham

Art Unit: 1709

REPLY TO OFFICE ACTION DATED APRIL 20, 2007

Commissioner for Patents

P.O. Box 1450

Arlington, VA 22313-1450

Dear Sir:

Further and favorable consideration of the above application is respectfully requested in view of the following amendments, and in view of the following remarks.